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SEMICONDUCTOR PROCESSING ARTICLE

ABSTRACT OF THE DISCLOSURE

- 5 A semiconductor processing article is characterized by
extended useful life. The article is used in a semiconductor furnace
system, particularly in a low pressure chemical vapor deposition
furnace for prolonged periods without requiring cleaning to remove
build-up film. The semiconductor processing article is a quartz body
characterized by a surface roughness having a first component with an
10 average deviation from a first mean surface of about 2.5 to 50 microns,
and a second component with an average deviation from a second
mean surface of about 0.25 to 5 microns. The processing article is
prepared for use in the furnace by mechanically blasting and
chemically etching the surface of the article.